

Title (en)

ION IMPLANTER OPERATING IN PULSED PLASMA MODE

Title (de)

IN GEPULSTEM PLASMA-MODUS FUNKTIONIERENDE IONEN-IMPLANTIERUNGSVORRICHTUNG

Title (fr)

IMPLANTEUR IONIQUE FONCTIONNANT EN MODE PLASMA PULSE

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Application

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Abstract (en)

[origin: WO2006003322A2] The invention relates to an ion implanter (IMP) comprising a pulsed plasma source (SPL), a substrate support plate (PPS) and a power supply (ALT) for said plate. The inventive implanter also comprises a capacitor C which is connected directly to the earth (E) and which is mounted downstream of the plate power supply (ALT). The invention also relates to a method of using said implanter.

IPC 8 full level

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Citation (search report)

See references of WO 2006003322A2

Citation (examination)

- EP 1111084 A1 20010627 - AXCELIS TECH INC [US]
- US 4937205 A 19900626 - NAKAYAMA ICHIRO [JP], et al

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